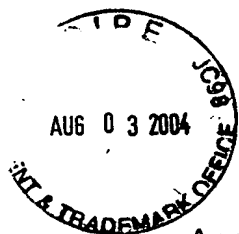


IFW



1021.39949VX1

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicants: F. ISSHIKI, et al

Serial No.: 10/669,329

Filed: September 25, 2003

For: LASER INTERFEROMETER DISPLACEMENT MEASURING  
SYSTEM, EXPOSURE APPARATUS, AND ELECTRON BEAM  
LITHOGRAPHY APPARATUS

Group: 2877

Examiner: M. Lyons

**AMENDMENT**

**MS Amendment**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450  
Sir:

August 3, 2004

In response to the Office Action dated May 3, 2004, please amend the  
above-identified application as follows.

**Amendments to the Claims**

**Remarks** are included following the amendments.